Ozone Production and Its Sensitivity to NOx and VOCs during LISTOS 2018

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Long Island Sound Tropospheric Ozone Study Meeting April 11, 2019





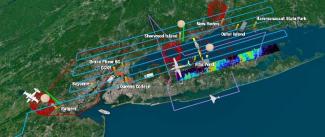
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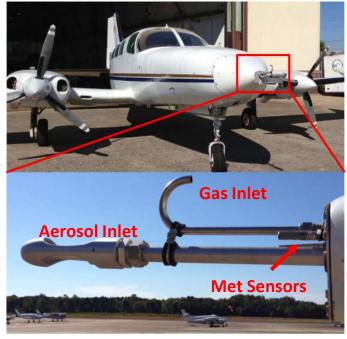








UMD Cessna 402B Research Aircraft





GPS Position (Lat, Long, Altitude)

Met (T, RH, P, wind speed/direction with a diferential GPS)

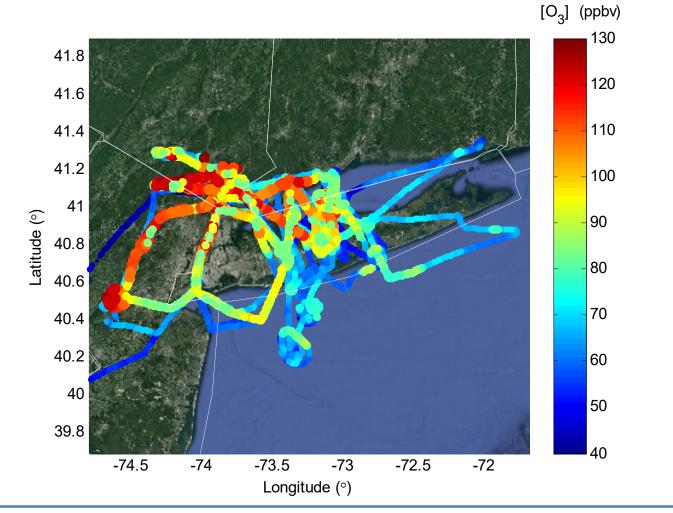
Trace gases:

- O₃: UV Absorption, modified TECO NO₂: Cavity Ring Down, Los Gatos NO/NOy: Chemiluminescence, modified TECO
- SO₂: Pulsed Fluorescence, modified TECO CH₄/CO₂/CO: Cavity Ring Down, Picarro HCHO: Laser Induced Fluorescence VOCs: grab samples with GC-FID

Aerosol Optical Properties:

Scattering: b_{scat} (@450, 550, 700 nm), Nephelometer Absorption: b_{ap} (@565 nm), PSAP Black Carbon: Aethalometer AE33

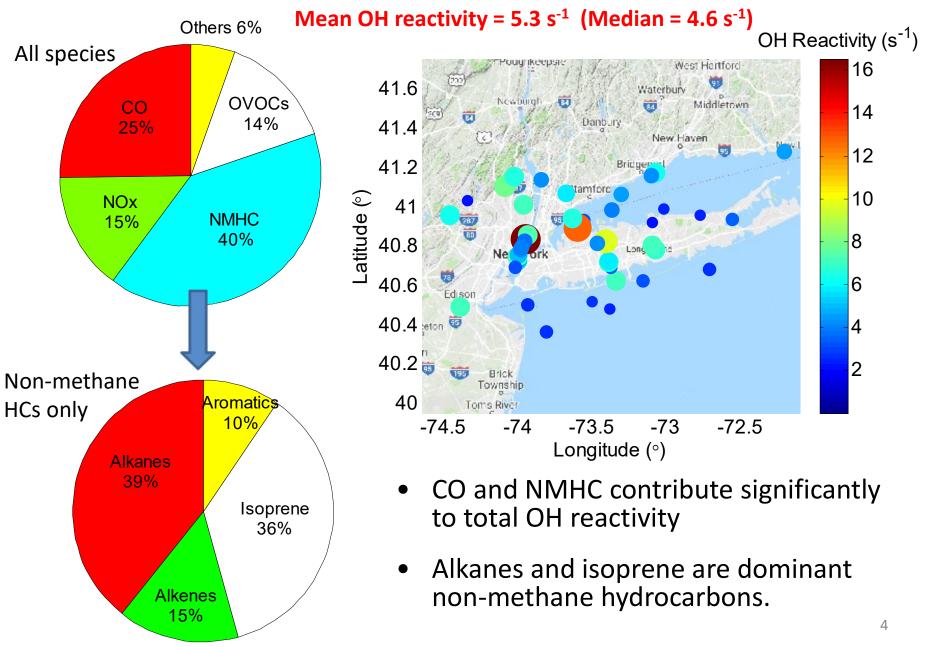
- 8 flights on 4 ozone days: July 1-2 & Aug. 15-16
- Data available at the NASA LISTOS archive: https://www-air.larc.nasa.gov/cgi-bin/ArcView/listos



UMD Cessna flights during LISTOS 2018

- Measurements of ozone and its precursors NOx and VOCs
- 1-minute average of ozone up to 130 ppb was observed in NYC/LIS.

OH Reactivity during LISTOS 2018



Box Model Simulations

- Mechanism: Regional Atmospheric Chemistry Mechanism, Version 2 (RACM2) (*Golliff et al., 2013*)
- Model constrained by measured chemical specie and meteorological parameters (T/P/RH/J values) along the flight tracks.
- Model output: OH, HO₂, RO₂ and other reactive intermediates.
- Modeled data points: 46 VOC samples during LISTOS 2018

We can use model results to calculate ozone production and its sensitivity to NOx and VOCs.

Photochemical Ozone Production, $P(O_3)$

 $HO_{2} + NO \rightarrow OH NO_{2}$ $RO_{2} + NO \rightarrow RO + NO_{2}$ $NO_{2} + hv \rightarrow NO + O_{3}$

 $P(O_3) = k_{NO+HO2} [NO][HO_2] + \sum_i k_{NO+RO2i} [NO][RO_{2i}]$

 $L(O_3) = k_{O1D+H2O}[O(^1D)][H_2O] + k_{HO2+O3}[O_3][HO_2]$ + $k_{OH+O3}[O_3][OH] + k_{OH+NO2+M}[OH][NO_2][M]$

Net photochemical $P(O_3)$: $P(O_3)_{net} = P(O_3) - L(O_3)$

P(O₃) Sensitivity to NOx and VOC

 $P(O_3)$ is a function of NOx and VOC reactivity as:

 $P(O_3) = KQ^{C1}[NO_x]^{C2}[VOC_R]^{C3}$

and the sensitivity of ozone production can be determined by an indicator, L_N/Q :

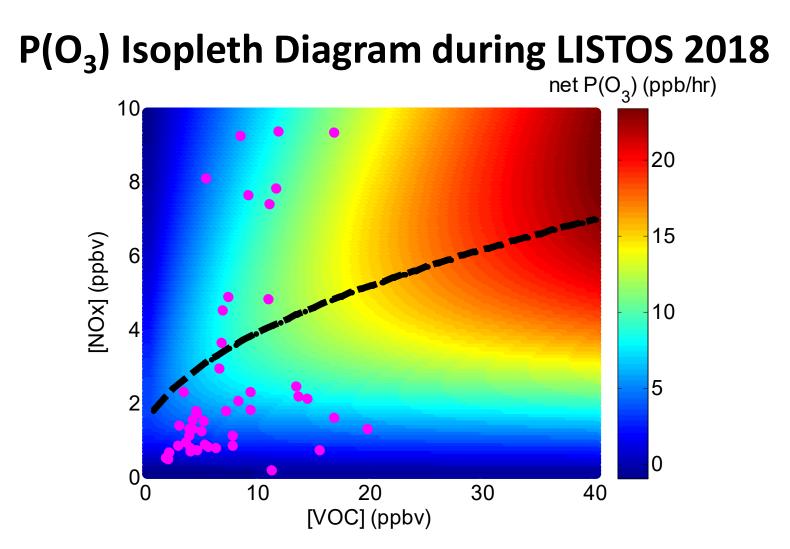
$$\frac{dlnP(O_3)}{dln[NOX]} = \frac{1 - 1.5 * L_N / Q}{1 - 0.5 * L_N / Q} \text{ and } \frac{dlnP(O_3)}{dln[VOCR]} = \frac{L_N / Q}{2 - L_N / Q}$$

where, L_N : Radical loss due to NOx;

Q: Total primary radical production

 $L_N/Q > 0.5 \rightarrow P(O_3)$ is VOC-sensitive $L_N/Q < 0.5 \rightarrow P(O_3)$ NOx-sensitive (Kleinman et al.

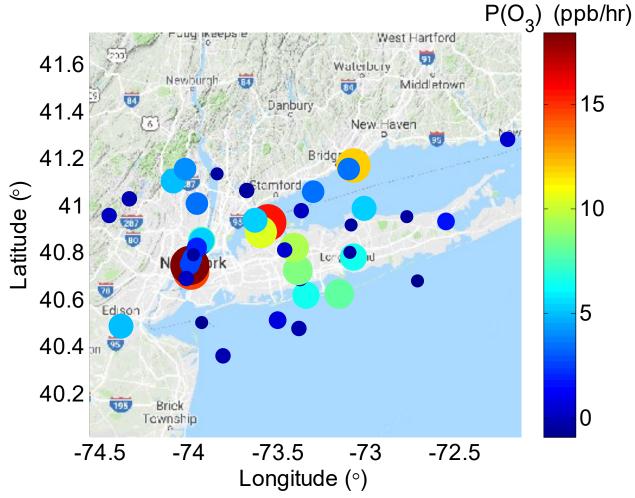
(Kleinman et al., 2001)



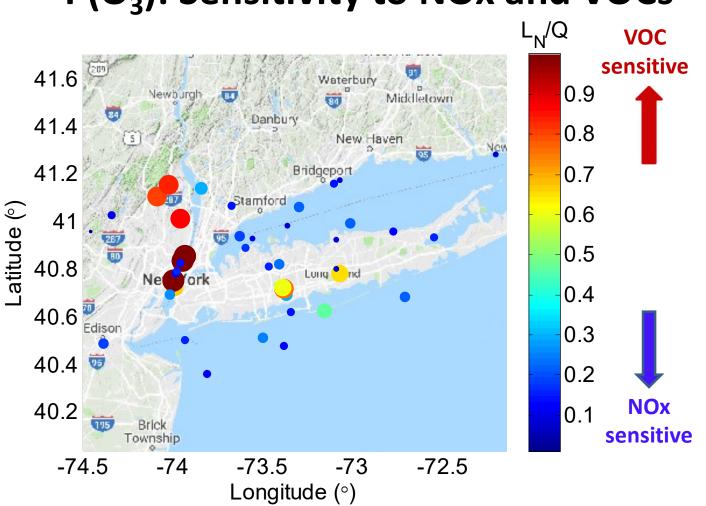
- Background: $P(O_3)$ as a function of NOx & VOCs based on mean met & chemical conditions
- Circles: data points with VOC measurements
- Most samples are NOx-sensitive with other samples to be VOC-sensitive
- Controlling both NOx and VOCs to reduce P(O₃)

Net P(O₃): Spatial Variation

Mean net $P(O_3) = 3.9 \text{ ppb/hr}$ (Median = 3.0 ppb/hr) $P(O_3)$ (ppb/hr)



- Each circle reprents the location where we collected VOC samples.
- In general higher P(O₃) near emission source regions



P(O₃): Sensitivity to NOx and VOCs

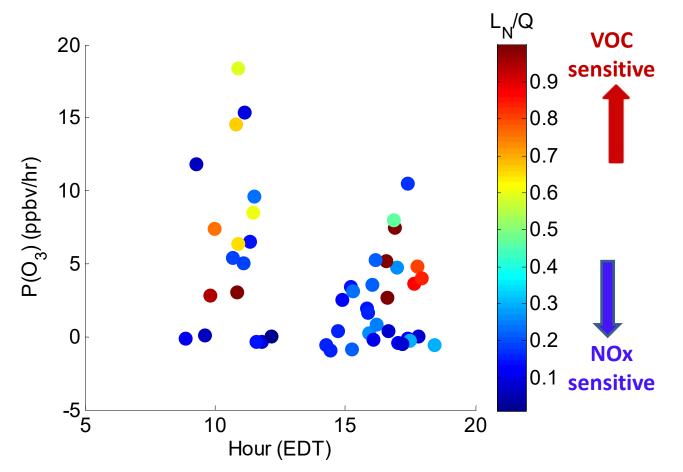
- In general VOC sensitive near emission sources
- NOx sensitive away from source regions.

Key Points

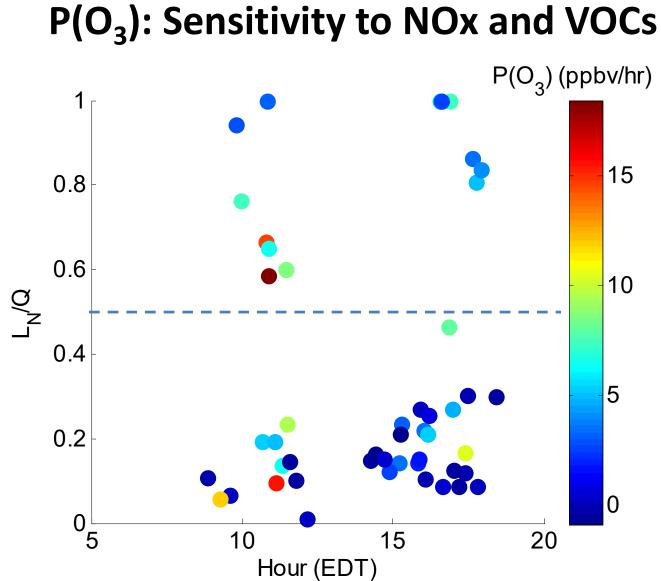
- Box modeling was conducted to study ozone production and its sensitivity to NOx and VOC using the aircraft data collected during LISTOS 2018.
- In general ozone production, or P(O₃) is VOC sensitive near emission sources and NOx sensitive away from source regions.
- Controlling both NOx and VOCs to reduce P(O₃) in NYC/LIS:
 - Reducing VOCs can reduce $P(O_3)$ in emission source regions.
 - Reducing NOx can reduce $P(O_3)$ in areas away from the source regions.

Backup slides

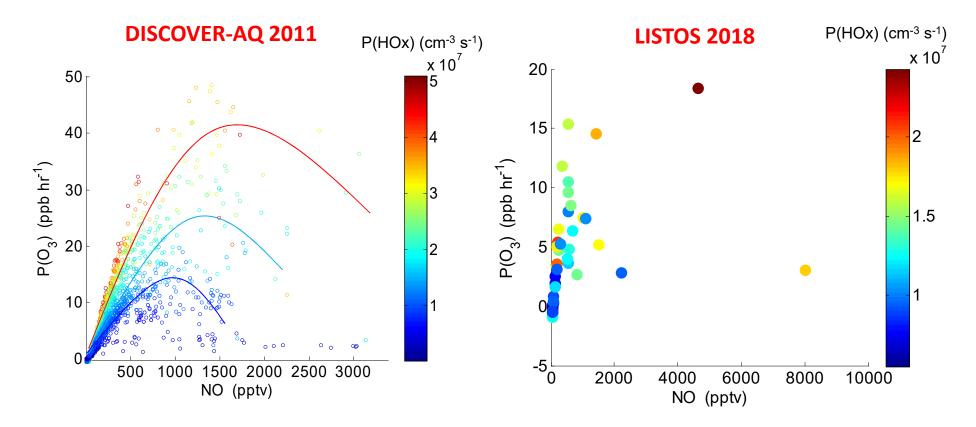
P(O₃): Diurnal Variation



• High $P(O_3)$ in both NOx and VOC sensitive regimes.



P(O₃): NO Dependence



- NO dependence of $P(O_3)$ as we would expect:
 - Higher P(O3) at higher P(HOx) or photochemical reacitivity
 - Lower [NOx] turning point with less P(JHOx) or photochemical reactivity